IEUVI
Optics Contamination / Lifetime Technical Working Group

San Jose, CA, USA
February 28, 2008

Chair:
Andrea Wüest, SEMATECH

Co-chairs:
AP: Yasuaki Fukuda, EUVA/Canon
US: Tom Lucatorto, NIST
Kevin Orvek, SEMATECH/Intel
Obert Wood, AMD

Advanced Materials Research Center, AMRC, International SEMATECH Manufacturing Initiative, and ISMI are servicemarks of SEMATECH, Inc. SEMATECH, and the SEMATECH logo are registered servicemarks of SEMATECH, Inc. All other servicemarks and trademarks are the property of their respective owners.

Organizational

- Sign-in list
- Not pre-registered:
  Walk-in registration form
- Non-US citizens, not pre-registered:
  Export Written Assurance Letter
- Evaluation form

SEMATECH
Accelerating the next technology revolution.

Confidentiality Notice
- Non-Confidential Meetings-

- **This is a Non-Confidential Meeting**
- **This meeting may be open to non-members**
- **If proprietary or confidential information is disclosed,**
  - The discloser does so at his/her own risk
  - The discloser does so with the knowledge that the audience may include non-members
  - SEMATECH will not accept presentation materials marked “confidential” or “proprietary” for distribution

SEMATECH
Accelerating the next technology revolution.

Export Compliance

- U.S. export regulations require Foreign Nationals to sign a "Written Assurance" that technical information will not be disclosed to Restricted Countries*
  - Not required of member personnel with confirmed registration
- "Foreign National" means anyone not a U.S. citizen, Legal Permanent Resident, or INS "protected alien"
- Foreign Nationals of Restricted Countries* may not attend without the approval of the SEMATECH Export Manager
  - Applies to all, even member personnel
- ***Albania, Armenia, Azerbaijan, Belarus, Cambodia, China (PRC), Cuba, Georgia, Iran, Iraq, Kazakhstan, Kyrgyzstan, Laos, Libya, Macau, Moldova, Mongolia, North Korea, Russia, Sudan, Syria, Tajikistan, Turkmenistan, Ukraine, Uzbekistan, Vietnam.**

Questions?

- Please see your meeting chairperson IF
  - **You are a Foreign National who did not sign an Export Written Assurance**
    - **Unless pre-registered and a member employee**
  - **You are a Foreign National of a Restricted Country**
  - **You have questions about confidentiality or export requirements**

SEMATECH
Accelerating the next technology revolution.

Agenda

San Jose, CA, February 28, 2008 – San Jose Hilton – Almaden Ballroom 1

Time	Topic	Speaker
7:45	**Breakfast**	
8:00	**Welcome and Introductions**	A. Wüest, SEMATECH
	Regional Updates / Critical issues	
8:10	• Asia / Pacific	Y. Fukuda, EUVA / Canon
8:20	• US	T. Lucatorto, NIST
	EUV Optics Contamination	
8:30	• Status of Optics Contamination in SFET	I. Nishiyama, Selete
8:50	• Neutral Cluster Modeling of the Reactivity of Coating Materials for EUV Optics	E. Bernstein, Colorado State U.
9:15	• Summary of EUV Optics Contamination Modeling Meeting	A. Wüest, SEMATECH
9:30	**Break**	
	EUV Resist Outgassing and Optics Contamination	
9:45	Introduction	K. Orvek, Intel/SEMATECH
9:50	Counting Molecules Approach	
	• How do we currently fare against SEMATECH, ASML and Nikon recommended levels?	K. Orvek, Intel/SEMATECH
	• How did we determine SEMATECH recommended level?	K. Orvek, Intel/SEMATECH
	• Should all molecules be counted? Do some not matter?	
	Albany data	G. Denbeaux, U. Albany
	NIST data	Shannon Hill, NIST
10:30	Witness Plate Testing Approach	
	• Plans for high-outgas calibration	K. Orvek, Intel/SEMATECH
	Albany Samples	G. Denbeaux, U. Albany
	IBM Samples	R. Allen, IBM
11:00	**Discussion**	K. Orvek, Intel/SEMATECH
11:45	**Adjourn**	

Rooms

- **Resist TWG**: Almaden Ballroom 1 (Same room)
- **Mask TWG**: Almaden Ballroom 2
- **Source TWG**: Santa Clara Room

SEMATECH
Accelerating the next technology revolution.

Next IEUVI Optics Contamination and Lifetime TWG Meeting

- EUVL Symposium, Lake Tahoe, CA, USA
- October 2, 2008
- Presentations will be available on www.ieuvi.org

SEMATECH
Accelerating the next technology revolution.

Evaluation

- Please fill out the Evaluation Forms
- Weekday of TWG at next SPIE Advanced Litho Conference?

SEMATECH
Accelerating the next technology revolution.

Thank you

Thank you very much for your participation and contribution!

SEMATECH
Accelerating the next technology revolution.